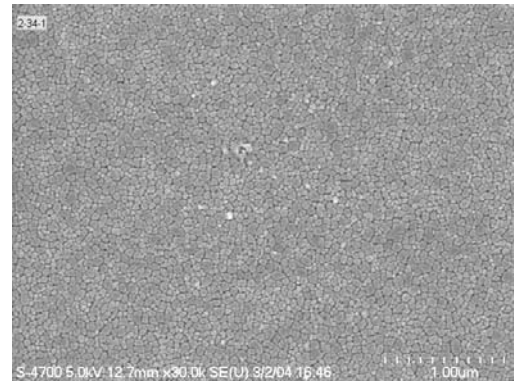
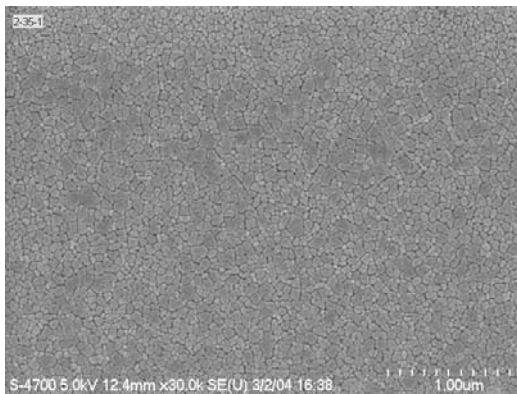


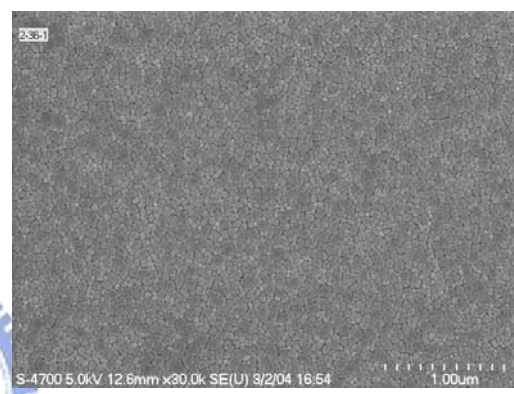
(a)



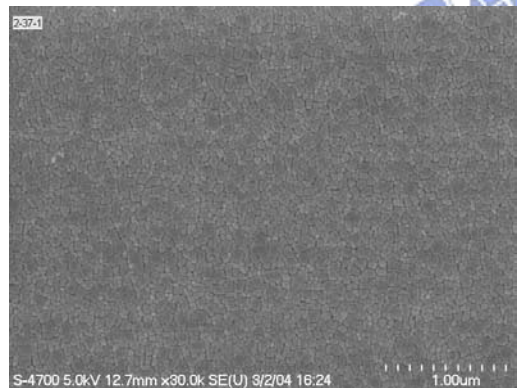
(b)



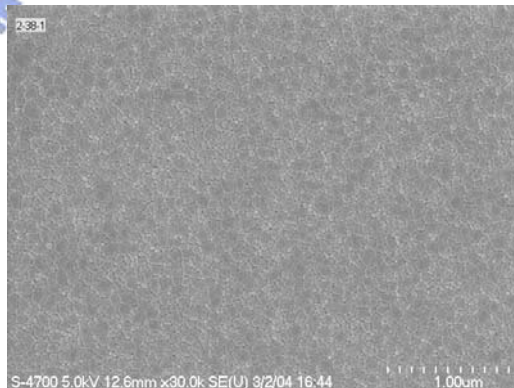
(c)



(d)

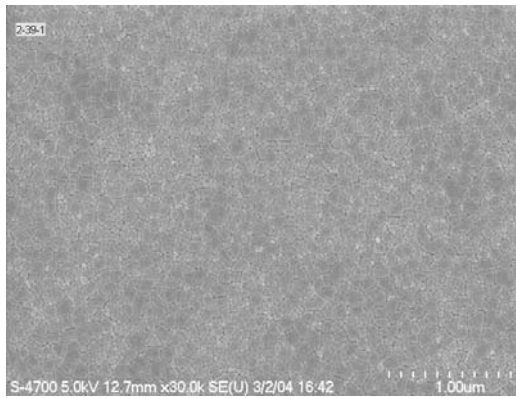


(e)

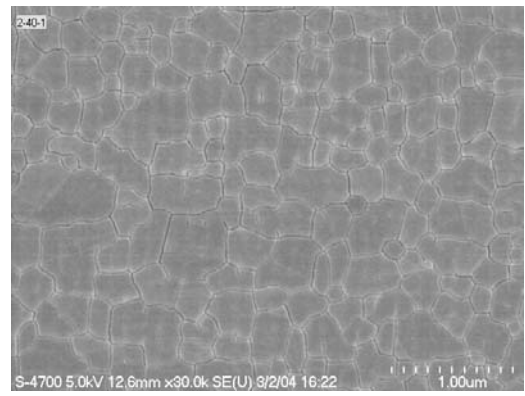


(f)

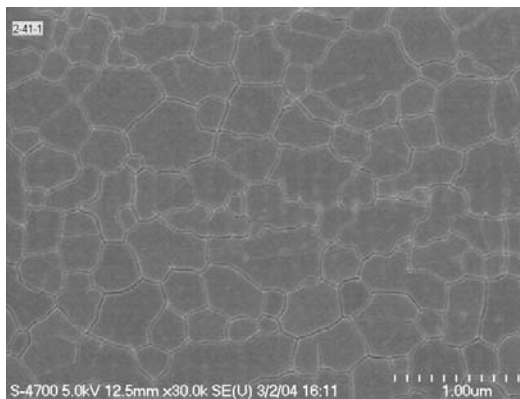
Fig. 2-18 SEM micrographs of excimer laser crystallized poly-Silicon films after Secco etching for 60sec treatment. The applied laser energy densities are (a) 330, (b) 340, (c) 350, (d) 360 (e) 370 (f) 380 mJ/cm^2 . The laser energy 950 mJ, frequency 300 Hz, power 285 W, scan speed 6 mm/sec, pitch 0.02mm, beam width 0.4 mm, pre treatment clean with HF 1% for 150sec



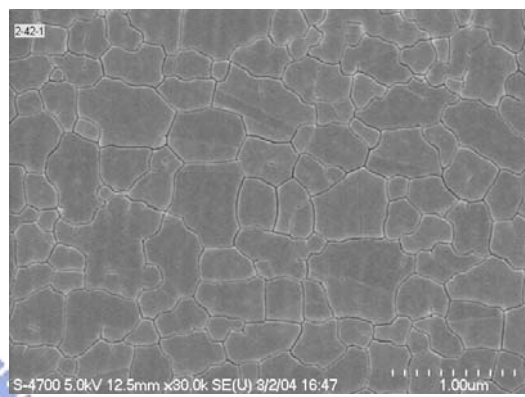
(a)



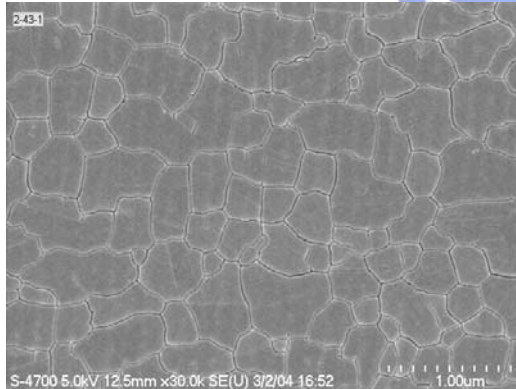
(b)



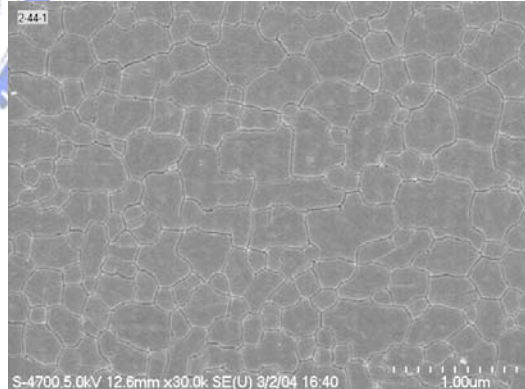
(c)



(d)



(e)



(f)

Fig. 2-19 SEM micrographs of excimer laser crystallized poly-Silicon films after Secco etching for 60sec treatment. The applied laser energy densities are (a) 390, (b) 400, (c) 410, (d) 420 (e) 430 (f) 440 mJ/cm^2 . The laser energy 950 mJ, frequency 300 Hz, power 285 W, scan speed 6 mm/sec, pitch 0.02 mm, beam width 0.4 mm, pre treatment clean with HF 1% for 150 sec